

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re United States Patent Application of:		)	Docket No.:	020732-97.668
		)		(7493)
Applicants:	RATH, Melissa K., et al.	)	Conf. No.:	4823
Application No.:	10/792,038	)	Art Unit:	1752
Date Filed:	March 3, 2004	)	Examiner:	LE, Hoa Van
Title:	COMPOSITION AND PROCESS FOR	)	Customer No.:	24239
	POST-ETCH REMOVAL OF	)		
	PHOTORESIST AND/OR	)		
	SACRIFICIAL ANTI-REFLECTIVE	)		
	MATERIAL DEPOSITED ON A	)		
	SUBSTRATE	)		

**AMENDMENT RESPONDING TO APRIL 19, 2007 OFFICE ACTION IN UNITED STATES PATENT APPLICATION NO. 10/792,038**

Mail Stop Amendment  
Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

Sir:

This responds to the April 19, 2007 Office Action in the above-identified application.

Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the April 19, 2007 Office Action are set out in the **Section II (Remarks)** hereof.